VE 320 Fall 2021

Introduction to Semiconductor Devices

Instructor: Rui Yang (杨睿)

Office: JI Building 434

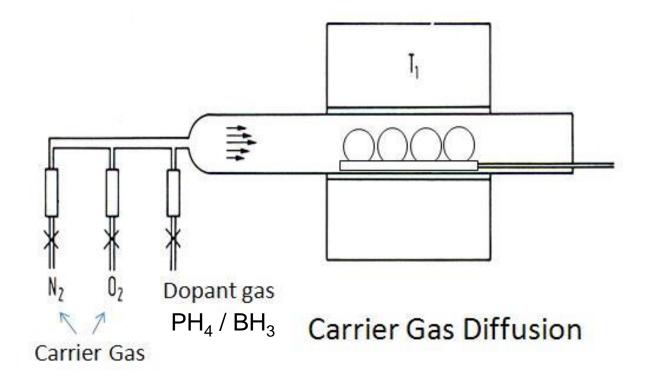
rui.yang@sjtu.edu.cn



Lecture 7

pn Junction (Chapter 7)

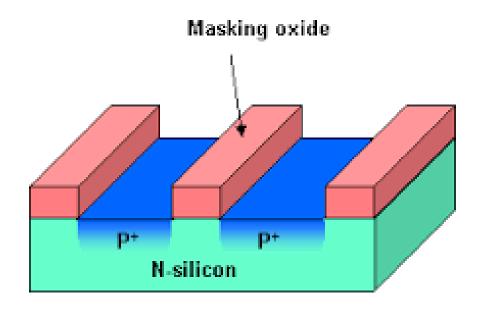
Doping by Thermal Diffusion



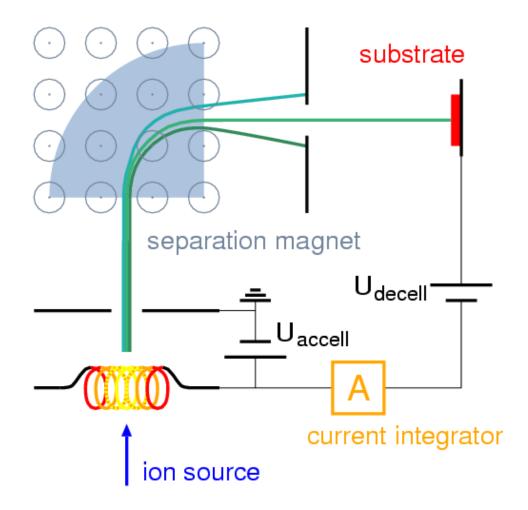
Doping by Thermal Diffusion



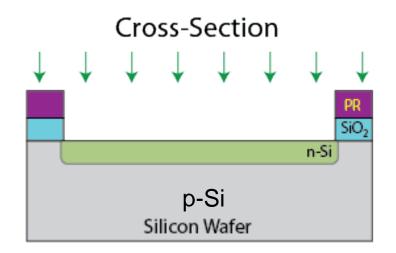
Doping by Thermal Diffusion

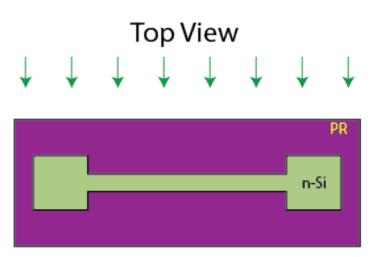


Doping by Ion Implantation



Doping by Ion Implantation

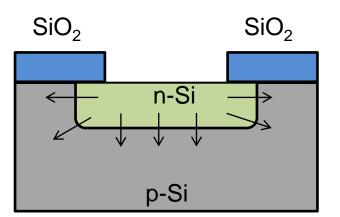




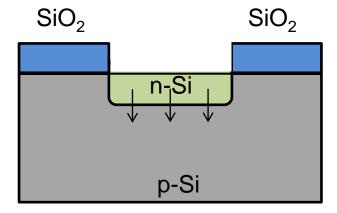
Followed by rapid thermal annealing:

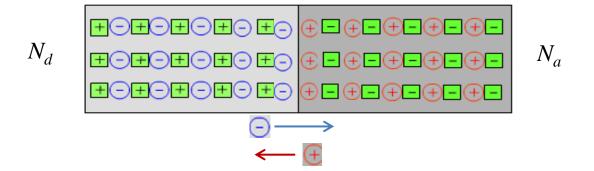
- chemically activate dopants
- not cause physical diffusion

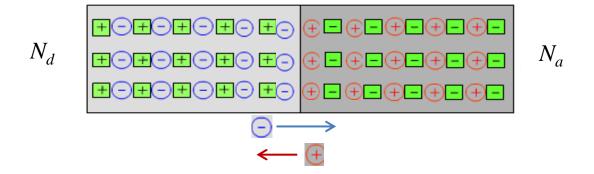
Doping by Thermal Diffusion



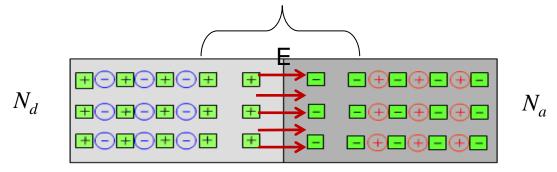
Doping by Ion Implantation

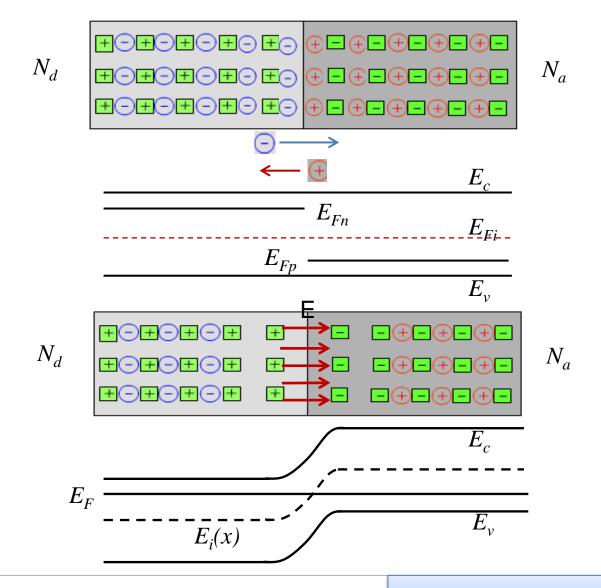






space charge region / depletion region





Built-in Potential

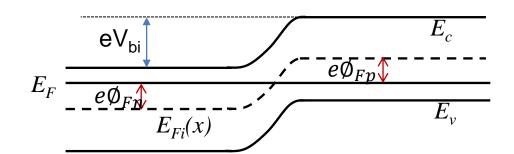
Assume complete ionization

$$n_0 = n_i \exp\left(\frac{E_F - E_{Fi}}{kT}\right) = n_i \exp\left(\frac{e\phi_{Fn}}{kT}\right) \longrightarrow \phi_{Fn} = \frac{-kT}{e} \ln\left(\frac{N_d}{n_i}\right)$$

$$p_0 = n_i \exp\left(\frac{E_{Fi} - E_F}{kT}\right) = n_i \exp\left(\frac{e\emptyset_{Fp}}{kT}\right) \longrightarrow \phi_{Fp} = +\frac{kT}{e} \ln\left(\frac{N_a}{n_i}\right)$$

$$\Rightarrow V_{bi} = |\emptyset_{Fn}| + |\emptyset_{Fp}| = \frac{kT}{e} ln\left(\frac{N_a}{n_i}\right) + \frac{kT}{e} ln\left(\frac{N_d}{n_i}\right) = \frac{kT}{e} ln\left(\frac{N_a N_d}{n_i^2}\right)$$

Example:
$$N_a = 10^{17} cm^{-3}$$
, $N_d = 10^{17} cm^{-3}$, $\Rightarrow V_{bi} = 0.026/e * \ln\left(\frac{10^{17} 10^{17}}{10^{20}}\right) = 0.84V$



Charge carrier distribution

$$n = n_i \exp\left(\frac{E_F - E_{Fi}(x)}{kT}\right) = N_d \exp\left(\frac{0.1eV}{0.026eV}\right) \approx \frac{N_d}{50}$$

$$p = n_i \exp\left(\frac{E_{Fi}(x) - E_F}{kT}\right) = N_a exp\left(\frac{0.1eV}{0.026eV}\right) \approx \frac{N_a}{50}$$

$$e\emptyset'_{Fn} = 0.1eV$$

$$e\emptyset'_{Fp} = 0.1eV$$

$$E_{r}$$

$$e\emptyset'_{Fp} = 0.1eV$$

$$E_{r}$$

$$e\emptyset'_{Fp} = 0.1eV$$

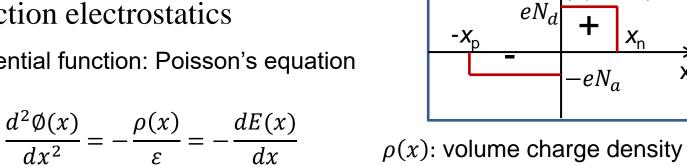
$$E_{r}$$

$$E_{r}$$

$$E_{r}$$

$$E_{r}$$

Potential function: Poisson's equation



 $= -\frac{e}{c} [N_d(x) - N_a(x) + p(x) - n(x)]$

Depletion region: no mobile charge n=p=0

$$\rho(x) = -eN_a \qquad -x_p < x < 0$$

$$\rho(x) = eN_d \qquad 0 < x < x_n$$

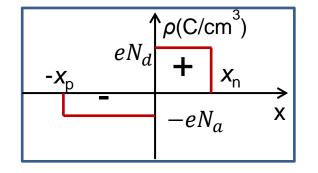
$$E_C \qquad eV_{bi} \qquad E_F$$

$$E_F \qquad e\phi_{Fp} \qquad E_F$$

 $\rho(C/cm^3)$

Potential function: Poisson's equation

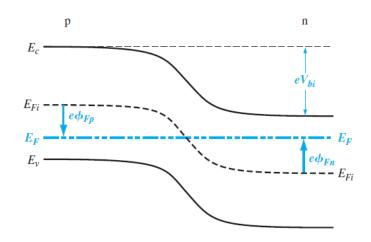
$$\frac{d^2\emptyset(x)}{dx^2} = -\frac{\rho(x)}{\varepsilon} = -\frac{dE(x)}{dx}$$
$$\rho(x) = -eN_a \qquad -x_p < x < 0$$



Electric field in the p region (in the depletion region): integration

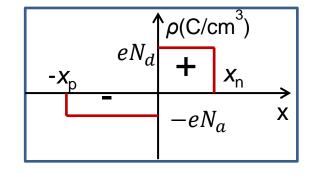
$$E = \int \frac{\rho(x)}{\epsilon_s} dx = -\int \frac{eN_a}{\epsilon_s} dx = \frac{-eN_a}{\epsilon_s} x + C_1$$

$$E = 0 \text{ at } x = -x_p \quad \text{So} \qquad E = \frac{-eN_a}{\epsilon_s} (x + x_p) \qquad -x_p \le x \le 0$$



Potential function: Poisson's equation

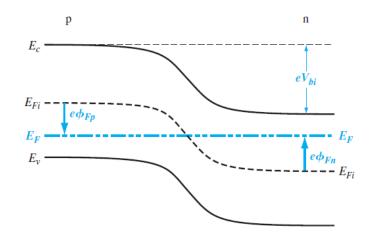
$$\frac{d^2\emptyset(x)}{dx^2} = -\frac{\rho(x)}{\varepsilon} = -\frac{dE(x)}{dx}$$
$$\rho(x) = -eN_a \qquad -x_p < x < 0$$



Electric field in the n region: integration

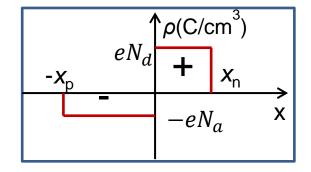
$$E = \int \frac{(eN_d)}{\epsilon_s} dx = \frac{eN_d}{\epsilon_s} x + C_2$$

$$E = 0 \text{ at } x = x_n \qquad \text{So} \qquad E = \frac{-eN_d}{\epsilon_s} (x_n - x) \qquad 0 \le x \le x_n$$



Potential function: Poisson's equation

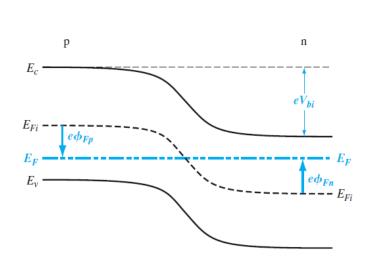
$$\frac{d^2\emptyset(x)}{dx^2} = -\frac{\rho(x)}{\varepsilon} = -\frac{dE(x)}{dx}$$
$$\rho(x) = -eN_a \qquad -x_p < x < 0$$

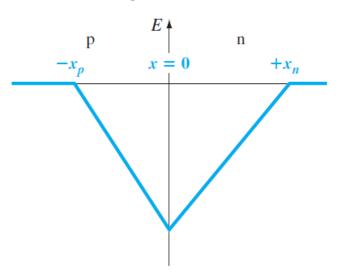


Electric field at x=0: continuous

$$N_a x_p = N_d x_n$$

the number of negative charges per unit area in the p region is equal to the number of positive charges per unit area in the n region





Potential: integrate electric field

In the p region (in the depletion region)

$$\phi(x) = -\int E(x)dx = \int \frac{eN_a}{\epsilon_s} (x + x_p)dx$$
$$\phi(x) = \frac{eN_a}{\epsilon_s} \left(\frac{x^2}{2} + x_p \cdot x\right) + C_1'$$

Only potential difference is important, so set potential=0 at $x=-x_{p}$

$$C_1' = \frac{eN_a}{2\epsilon_s} x_p^2$$

$$\phi(x) = \frac{eN_a}{2\epsilon_s} (x + x_p)^2 \qquad (-x_p \le x \le 0)$$

In the n region

$$\phi(x) = \int \frac{eN_d}{\epsilon_s} (x_n - x) dx = \frac{eN_d}{\epsilon_s} \left(x_n \cdot x - \frac{x^2}{2} \right) + C_2'$$

Potential is continuous at x=0

$$C_2' = \frac{eN_a}{2\epsilon_s} x_p^2$$

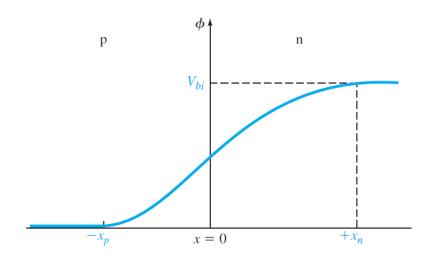
$$\phi(x) = \frac{eN_d}{\epsilon_s} \left(x_n \cdot x - \frac{x^2}{2} \right) + \frac{eN_a}{2\epsilon_s} x_p^2 \qquad (0 \le x \le x_n)$$

Potential: quadratic function of distance

$$V_{bi} = |\phi(x = x_n)| = \frac{e}{2\epsilon_s} (N_d x_n^2 + N_a x_p^2)$$

Potential energy

$$E = -e\phi$$



Preciously we have
$$N_a x_p = N_d x_n$$
 \longrightarrow $x_p = \frac{N_d x_n}{N_a}$

From
$$V_{bi} = |\phi(x = x_n)| = \frac{e}{2\epsilon_s} (N_d x_n^2 + N_a x_p^2)$$

We have
$$\chi_n = \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_a}{N_d} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2}$$

Space charge width, or the width of the depletion region, extending into the n-type region for the case of zero applied voltage

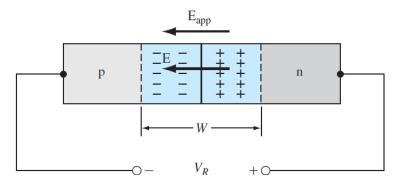
$$x_p = \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_d}{N_a} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2}$$
 In the p-type region

Total depletion or space charge width

$$W = \chi_n + \chi_p$$

$$= \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2}$$

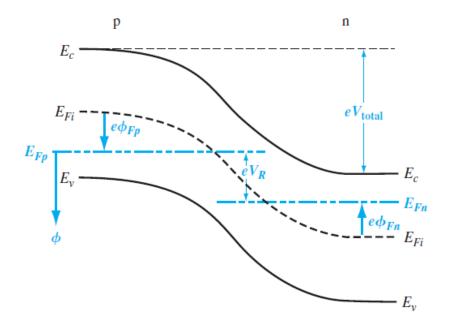
Reverse applied bias: Fermi energy no longer constant



$$V_{\text{total}} = |\phi_{Fn}| + |\phi_{Fp}| + V_R$$
$$= V_{bi} + V_R$$

No longer thermal equilibrium

Reverse applied bias: Fermi energy no longer constant



Space charge region: electric field increase impurity concentration not changed

→ Space charge width Wincreases

$$W = \left\{ \frac{2\epsilon_s(V_{bi} + V_R)}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2}$$

Reversed applied bias: Fermi energy no longer constant

Electric field:

$$E = \frac{-eN_a}{\epsilon_s}(x + x_p) \qquad -x_p \le x \le 0$$

$$E = \frac{-eN_d}{\epsilon_s}(x_n - x) \qquad 0 \le x \le x_n$$

Maximum electric field: x=0, metallurgical junction

$$E_{\max} = \frac{-eN_dx_n}{\epsilon_s} = \frac{-eN_ax_p}{\epsilon_s}$$

$$E_{\text{max}} = -\left\{\frac{2e(V_{bi} + V_R)}{\epsilon_s} \left(\frac{N_a N_d}{N_a + N_d}\right)\right\}^{1/2}$$

$$W = \left\{ \frac{2\epsilon_s (V_{bi} + V_R)}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2}$$

$$E_{\text{max}} = \frac{-2(V_{bi} + V_R)}{W}$$

Junction capacitance

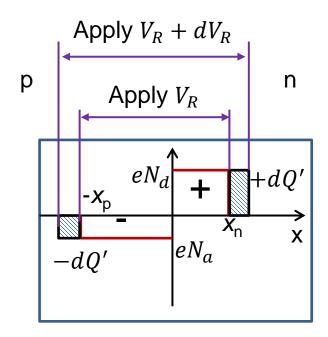
$$C' = \frac{dQ'}{dV_R}$$

$$dQ' = eN_d dx_n = eN_a dx_p$$

$$x_n = \left\{ \frac{2\epsilon_s(V_{bi} + V_R)}{e} \left[\frac{N_a}{N_d} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2}$$

$$C' = \frac{dQ'}{dV_R} = eN_d \frac{dx_n}{dV_R}$$

$$C' = \left\{ \frac{e\epsilon_s N_a N_d}{2(V_{bi} + V_R)(N_a + N_d)} \right\}^{1/2}$$



Depletion layer capacitance

pn Junction with reverse bias

• One-sided junction: If $N_a >> N_d$, the junction is a p⁺n junction

$$W pprox \left\{ rac{2\epsilon_s (V_{bi} + V_R)}{eN_d}
ight\}^{1/2}$$
 $X_p \ll X_n$ $W pprox X_n$

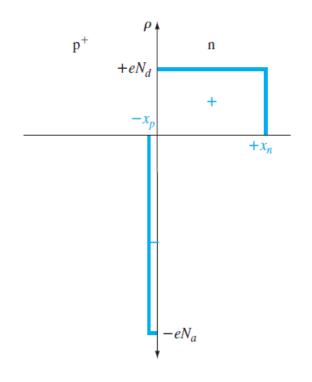
Almost the entire space charge layer extends into the low-doped region of the junction.

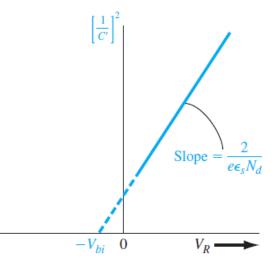
$$C' pprox \left\{ rac{e \epsilon_s N_d}{2(V_{bi} + V_R)}
ight\}^{1/2}$$

$$\left(\frac{1}{C'}\right)^2 = \frac{2(V_{bi} + V_R)}{e\epsilon_s N_d}$$

Assume: uniform doping in both semiconductor regions, the abrupt junction approximation, and a planar junction.

 $V_{\rm bi}$ and $N_{\rm d}$ can be determined

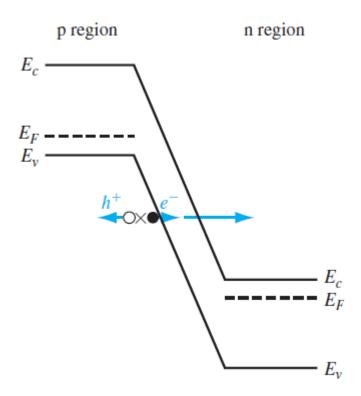




Reverse bias: breakdown at large voltage
 Zener effect and the avalanche effect

Zener breakdown: tunneling mechanism.

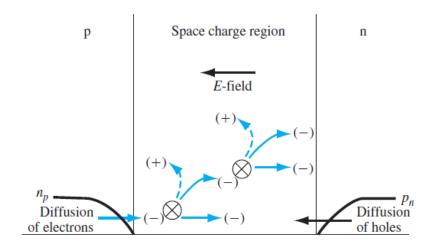
- In highly doped pn junctions
- Conduction and valence bands on opposite sides of the junction are sufficiently close during reverse bias
- Electrons may "tunnel" directly from the valence band on the p side into the conduction band on the n side.

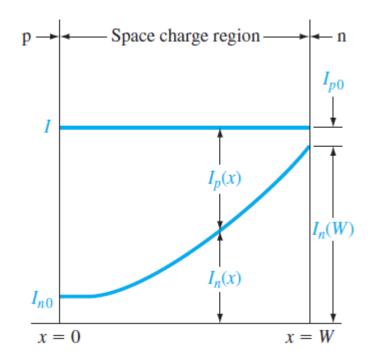


Reverse bias: breakdown at large voltage
 Zener effect and the avalanche effect

Avalanche breakdown: collision, dominant mechanism

- Electrons and/or holes, moving across the space charge region, acquire sufficient energy from the electric field to create New electron—hole pairs by colliding with atomic electrons within the depletion region
- Electrons and holes move in opposite directions due to the electric field and thereby create a reverse-biased current
- Avalanche: the newly generated electrons and/or holes may acquire sufficient energy to ionize other atoms-> more and more

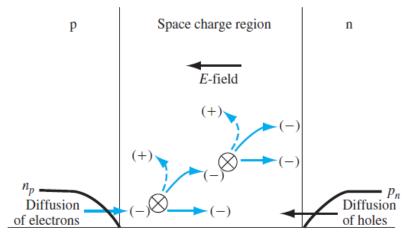






Reverse bias: breakdown at large voltage
 Zener effect and the avalanche effect

Avalanche breakdown: collision, dominant mechanism





Avalanche breakdown:

Reverse-biased electron current I_{n0} enters the depletion region at x = 0,

At
$$x=W$$
,

Integrate:

$$I_n(W) = M_n I_{n0}$$

where M_n is a multiplication factor

Hole current: large at x=0

Total current: constant through the pn junction

Incremental electron current $dI_n(x) = I_n(x)\alpha_n dx + I_p(x)\alpha_p dx$

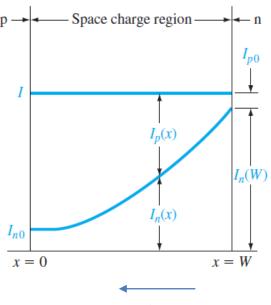
 α_n and α_p are the ionization rates, or the number of electron-hole pairs generated per unit length

Total current is a constant $I = I_n(x) + I_p(x)$

$$\frac{dI_n(x)}{dx} + (\alpha_p - \alpha_n)I_n(x) = \alpha_p I$$

Assume electron and hole ionization rates are equal $\alpha_n = \alpha_p \equiv \alpha$

$$I_n(W) - I_n(0) = I \int_0^W \alpha \, dx$$



E field

Avalanche breakdown:

$$\frac{M_n I_{n0} - I_n(0)}{I} = \int_0^W \alpha \, dx$$

Since $M_n I_{n0} \approx I$ and since $I_n(0) = I_{n0}$

$$1 - \frac{1}{M_n} = \int_0^W \alpha \, dx$$

Avalanche breakdown: *M*_n->∞

$$\int_0^W \alpha dx = 1$$

For one-sided p⁺n junction:

$$\int_0^w \alpha dx = 1$$

$$E_{\text{max}} = \frac{eN_d x_n}{\epsilon_s}$$

Depletion width:

$$x_n \approx \left\{ \frac{2\epsilon_s V_R}{e} \cdot \frac{1}{N_d} \right\}^{1/2}$$

Breakdown voltage:

$$V_B = \frac{\epsilon_s E_{\text{crit}}^2}{2eN_B}$$

